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Ni, Ti, and Fe Aluminides; 4.3 Diffusion Mechanisms in Intermetallics; 4.4 Experimental Results on Bulk Diffusion in Ordered Aluminides; 4.5 Discussion of Lattice Diffusion in Intermetallics; 4.6 Grain Boundary Diffusion; 4.7 Summary; Acknowledgments; References; Chapter 5. Diffusion Barriers in Semiconductor Devices/Circuits; 5.1 Introduction; 5.2 Diffusion Barriers from the 1960s Through the 1990s 5.3 Brief Review of Diffusion and the Influencing Material Factors 5.4 Diffusion Barrier Materials; 5.5 New Concepts in Affecting APDB Behavior at the Interfaces; 5.6 Brief Discussion of an APDB for Low-k ILD Materials; 5.7 Summary; References; Chapter 6. Reactive Phase Formation: Some Theory and Applications; 6.1 Introduction; 6.2 Theoretical Considerations; 6.3 Practical Problems in Electronic Technology; 6.4 Conclusions; Acknowledgments; References; Chapter 7. Metal Diffusion in Polymers and on Polymer Surfaces; 7.1 Introduction 7.2 Diffusion During Nucleation and Growth of Metal Films on Polymers 7.3 Metal-Polymer Interaction; 7.4 Diffusion in the Polymer Bulk; 7.5 Summary and Conclusions; Acknowledgments; References; Chapter 8. Measurement of Stresses in Thin Films and Their Relaxation; 8.1 Introduction; 8.2 Measurement Techniques; 8.3 Stress Relaxation; 8.4 Conclusion; References; Chapter 9. Electromigration in Cu Thin Films; 9.1 Introduction; 9.2 Cu Interconnection Integration; 9.3 Test Structure and Experiment; 9.4 Microstructure; 9.5 Theory; 9.6 Resistance and Void Growth; 9.7 Fast Diffusion Paths 9.8 Lifetime Distribution

Sommario/riassunto

This new game book for understanding atoms at play aims to document diffusion processes and various other properties operative in advanced technological materials. Diffusion in functional organic chemicals, polymers, granular materials, complex oxides, metallic glasses, and quasi-crystals among other advanced materials is a highly interactive and synergic phenomenon. A large variety of atomic arrangements are possible. Each arrangement affects the performance of these advanced, polycrystalline multiphase materials used in photonics, MEMS, electronics, and other applications of current and deve
